

ABSTRACT OF THE DISCLOSURE

The invention concerns a photolithography fabrication method enabling production of patterns in a photosensitive resin layer (601) placed on a substrate (600). The patterns (607) comprise flanks (608) 5 inclined relative to a normal (\vec{n}) relative to the principal plane of the substrate and which have an angle of inclination (θ) far greater to that of the patterns obtained according to the prior art.

The invention also concerns a device allowing said 10 method to be executed.

Figure 13A.